

EDA Needs for FPGA

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Outline

- Overview
- Desired EDA flow
- Altera's Needs
- Future Directions

Times Have Changed



SOPC Builder



OpenCL

1990s

2010s

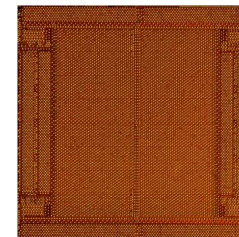
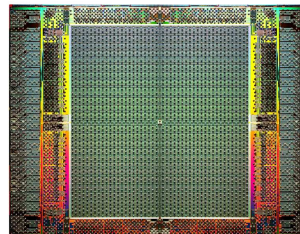
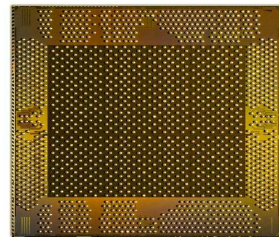
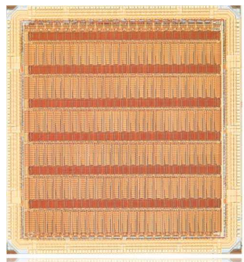
Glue Logic

Heterogeneous Capabilities

High Integration/
Bandwidth

Hardened Subsystems

Cortex-A9
MPCore



Flex 6000
30μ process

Stratix I
130nm process

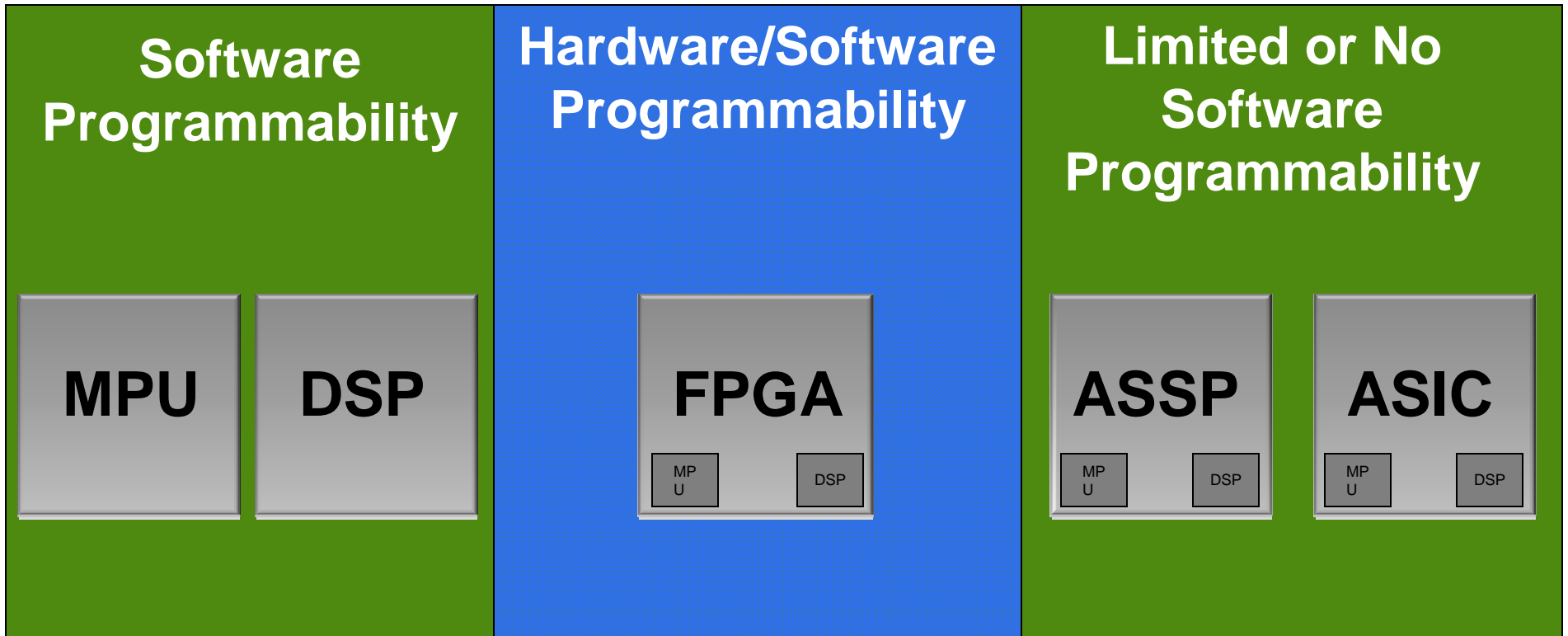
Stratix IV
40nm process

Stratix V
28nm process

SoC FPGA
28nm process



Silicon Convergence



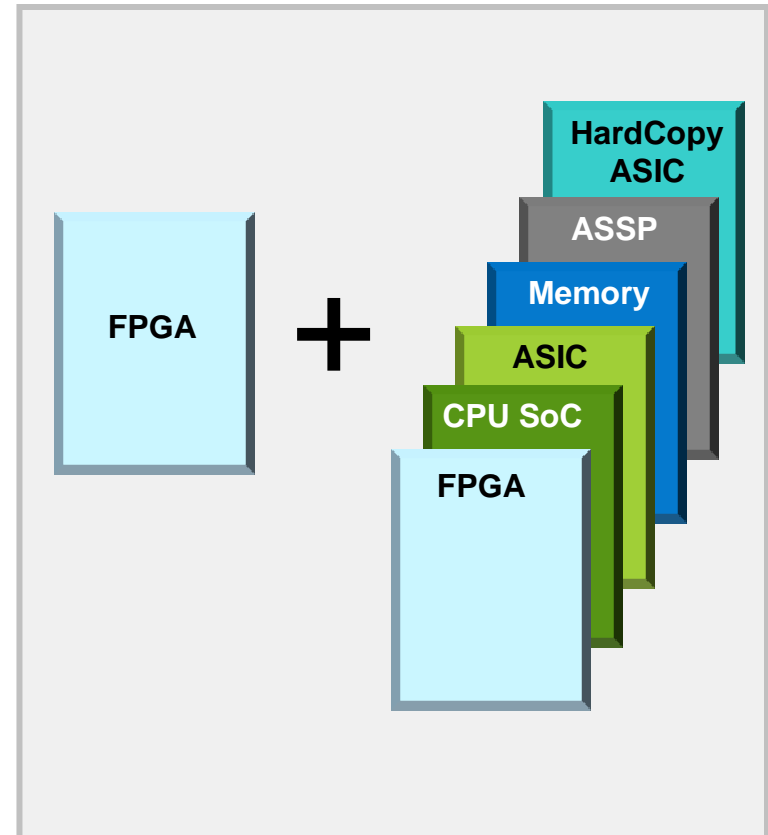
***FPGA Platforms Ideally Positioned
for Convergence***

Silicon Convergence Laying Foundation for 3D

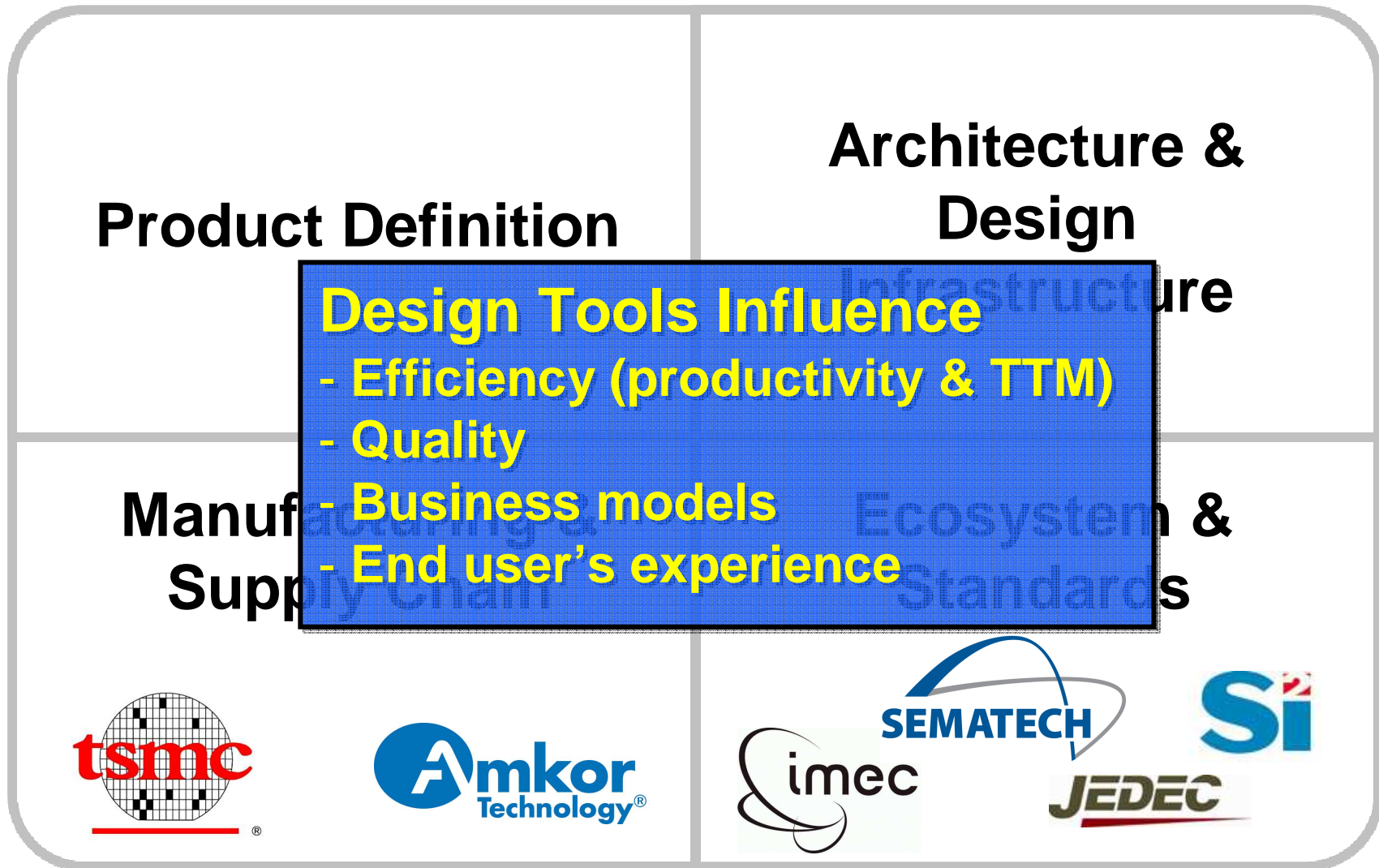
- Bandwidth expansion
 - High-bandwidth chip-to-chip interface (JEDEC wide IO interface)
 - Optical interconnect
- Additional processing capabilities
 - Memory enhancement
- Product feature set expansion and time-to-market
 - Derivative products
- Energy efficiency
- Integration
 - Fewer components

Altera's 3D Silicon Vision

- Customer & application driven heterogeneous system integration in package
 - Mix and match silicon IP
 - Integrated design flow
 - Integrated system test methodology
- Maximum system performance
- Minimum system power
- Smallest form factor
- Reduced system cost



Altera's Product Development Strategy





Altera and TSMC Jointly Develop World's First Heterogeneous 3D IC Test Vehicle Using CoWoS™ Process

Altera Leveraging TSMC's CoWoS Manufacturing and Assembly Process for Development of Next-Generation 3D Devices

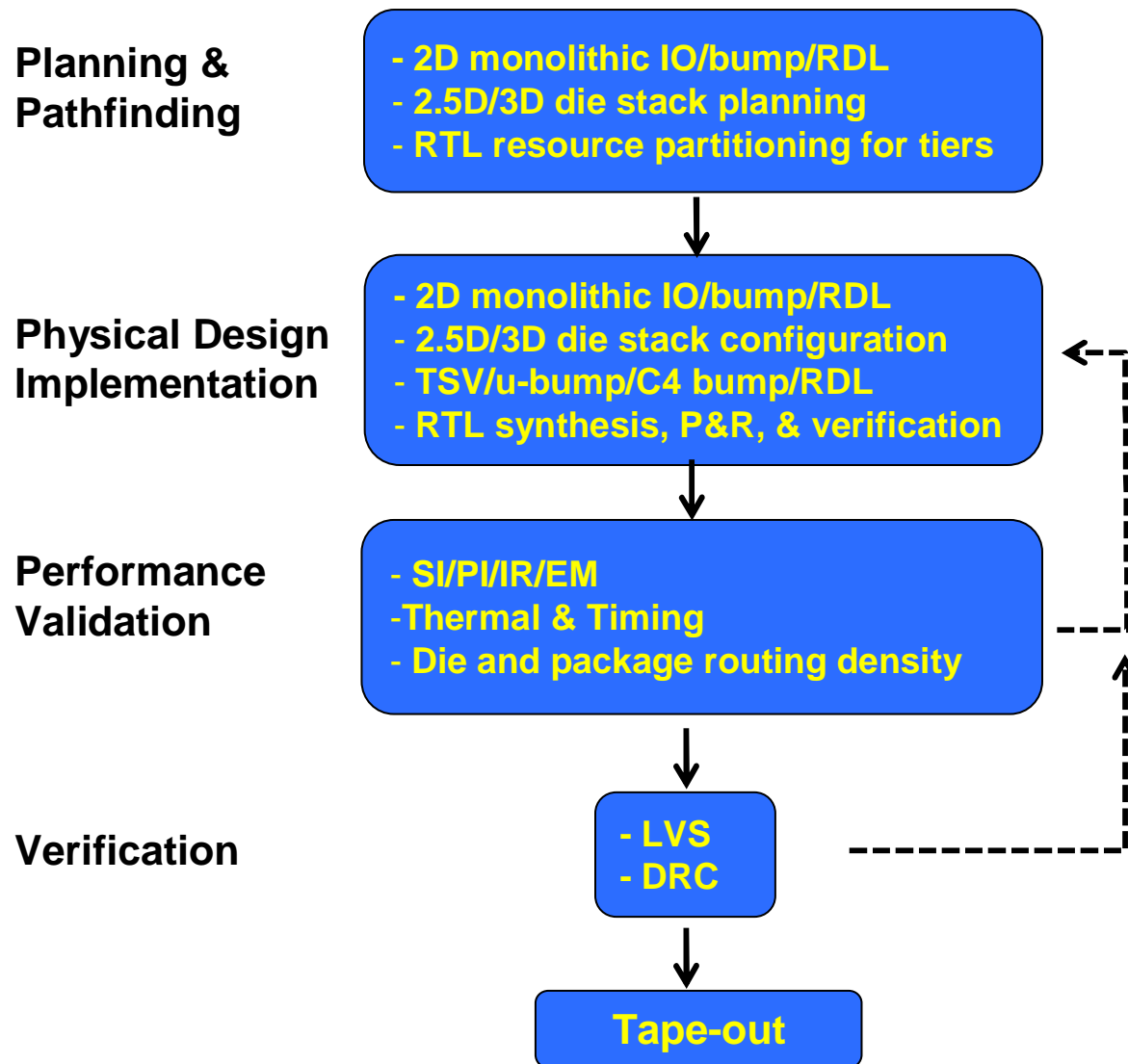
San Jose, Calif., and Hsinchu, Taiwan, March 22, 2012—Altera Corporation (Nasdaq: ALTR) and TSMC (TWSE: 2330, NYSE: TSM) today announced the joint development of the world's first heterogeneous 3D IC test vehicle using TSMC's Chip-on-Wafer-on-Substrate (CoWoS) integration process. Heterogeneous



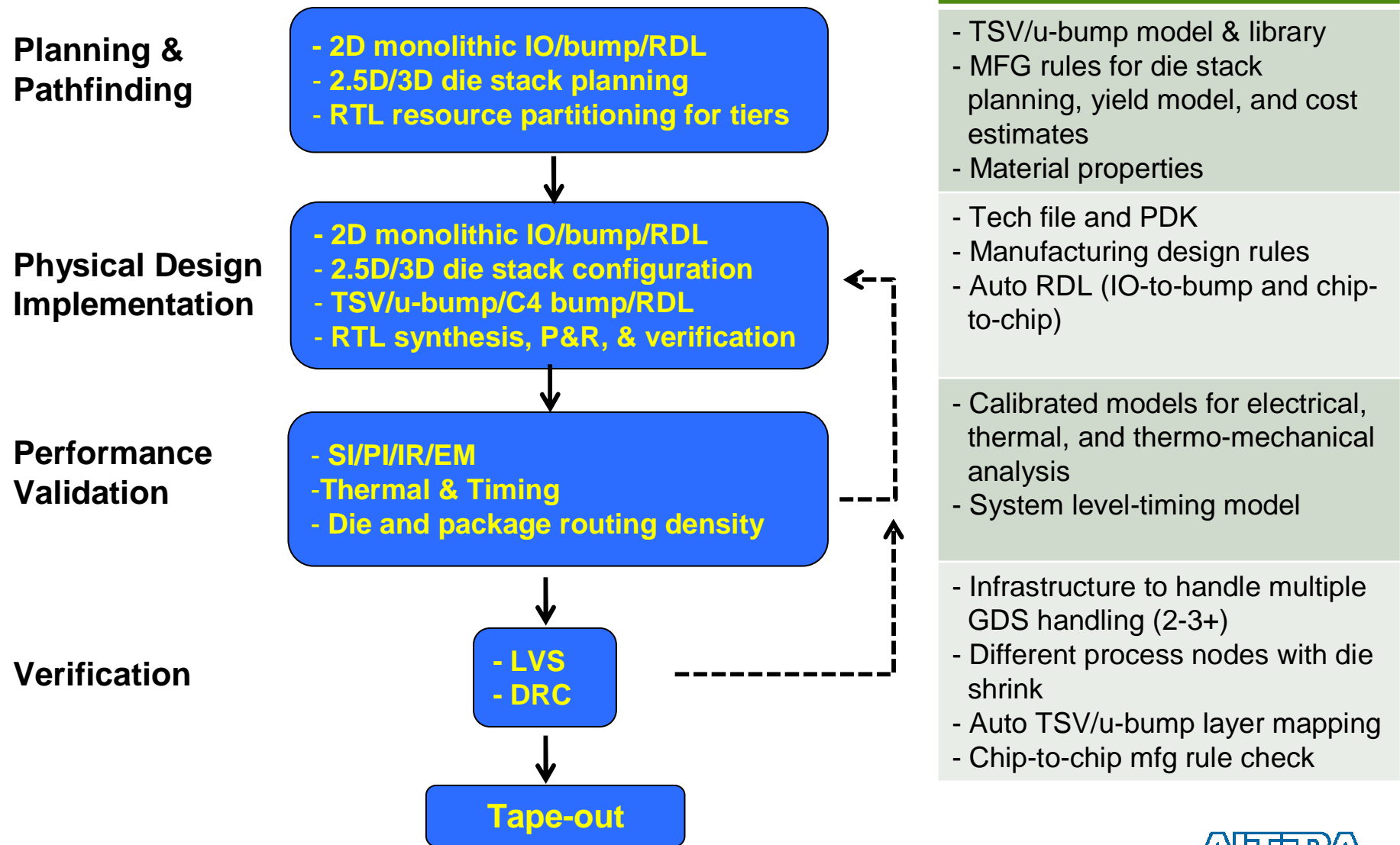
CoWoS: Chip on Wafer on Substrate



Desired EDA Flow for 3D Integration



Desired EDA Flow for 3D Integration



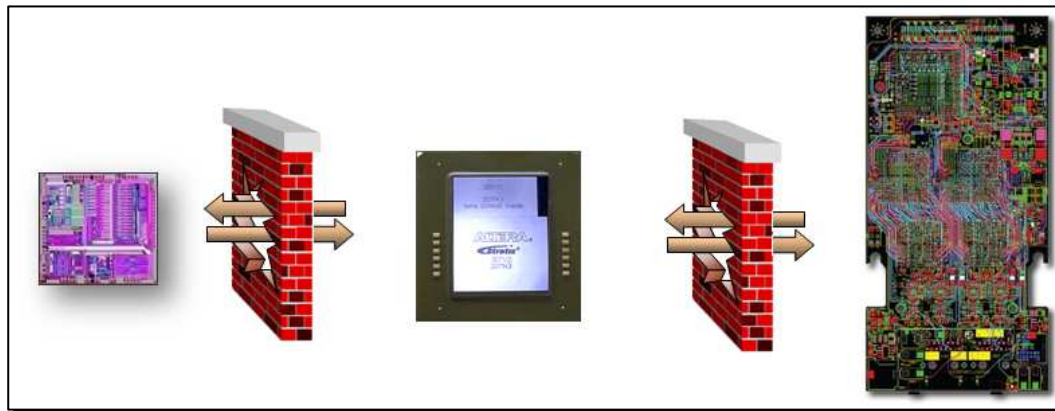
EDA Gaps

Flow exists
 Existing flows can be adapted
 Needs EDA support

Focus Areas	Path finding	Tier Design & Verification	Die Stack Verification and Perf. Validation
Design Partitioning & Chip-Package Co-Design			
Abstract Views			
Physical, Functional, and Timing Verification			
Connectivity Management			
SI/PI Analysis			
Thermal Analysis			
Thermo-mechanical Assessment			
Others: data exchange, scalability of database, etc.			

Pathfinding for Early Assessment

- Stacking configurations and chip-package interaction
 - System requirements => partitioning => tier requirements
 - Thermal and thermo-mechanical analysis based on macro models (effective material properties)



- 3D product specification
 - Architectural, functional, electrical, and test
 - Structural (intra-tier, inter-tier, and TSV/u-bump/bump planning)

Pathfinding for Early Assessment (Gaps)

- Existing RTL-to-GDS and Die/Package co-design flows are too cumbersome for quick and cross-functional what if analysis

Pathfinding for Early Assessment (Gaps)

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Physical Design Implementation: Tier Planning

- Floor planning
 - Application mapping
 - Dependencies among application specific hard/soft IPs
 - Use model
- TSV, u-bump, and bump planning
 - Intra- and inter-tier connectivity and performance optimization
- Manufacturing and keep-out rules

Physical Design Implementation (Gaps)

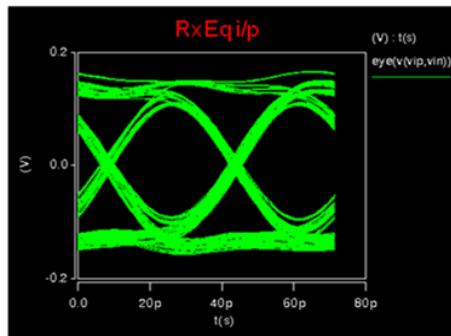
- DRC and LVS of individual tier and tier-to-tier interface (divide and conquer strategy)
 - Custom ad hoc methods invented on the fly vs. standard approach for tier-to-tier DRC/LVS
 - Challenges with multi-vendor or mixed-technology integration
- Visualization for debugging and FA
 - Navigating through different databases
- Managing database size and process shrinks

System Level Performance Validation (Gaps)

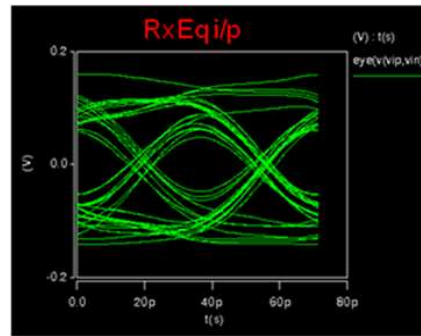
- Multi die power sign off is challenging due to large database sizes
 - Basic EDA infrastructure exists for abstracting die's (e.g CPM), but these are yet to evolve completely in mainstream flows
- Multi die STA is extremely challenging in 3D IC while complexity is manageable in 2.5D IC
- Multi die connectivity management for system level LVS
 - More convergence between IC schematics tools and SIP tools desired to bridge the gap between chip and system

System Level Performance Validation (Gaps)

- Chip-to-chip timing closure: SPICE & STA
- Signal integrity analysis
 - TSV and chip-to-chip interconnect coupling and cross talk
 - High speed chip-to-chip signaling loss



High-speed IO –
Monolithic Solution



High-speed IO –
Through Interposer

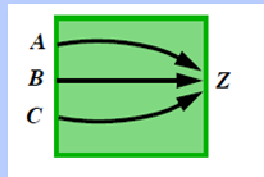
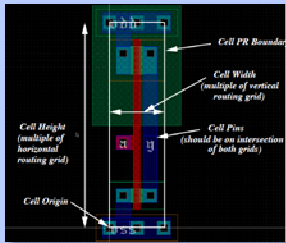
- PDN and Thermal

Future Trends

Extension of Existing Standards and Known Good Methods for Die-Stacking

Standard Cells

- ❑ Physical, Logical, & Abstract Views
- ❑ Timing, Power, & Parasitic
- ❑ GDSII, RTL, LEF, LIB, & TLF



```

Library Exchange Format (LEF)

Macro Pin Statement
PIN pinName
FOREIGN foreignPinName [STRUCTURE {pt {orient}}] :
[DIRECTION {INPUT | OUTPUT | BISTATE} | INOUT | FEEDTHRU] :
[USE { SIGNAL | ANALOG | POWER | GROUND | CLOCK } :]
[SHAPE { ABUTMENT | RING | FEEDTHRU } :]
[MUSTION pinName :]
{PORT
[CLASS {NONE | CORE} :]
[layerGeometries] ...
END} ...
END pinName

Macro Obstruction Statement
OBS
{ LAYER layerName [SPACING minSpacing | DESIGNRULEWIDTH value] :
RECT pt pt :
POLYGON pt pt pt pt ... :
END
    
```

IP

- ❑ IP-XACT/IEEE Std 1685
 - Hardware information
 - Software views, file lists, protocol standardization
 - Describes the interface to IPs, but not functionality
- ❑ In many cases
 - tool centric
 - determined by customers

Stacked IC

- ❑ Design & verification of each tier & overall system
- ❑ Tier-to-tier interface
 - Electrical
 - Functional
 - Physical
 - Timing
- ❑ Data format
 - Verification
 - Thermal
 - Thermo-mechanical
 - Chip-package design

Convergence in Manufacturing

- Die stacking approaches and design rules are converging
 - Flavors integration
 - TSV and micro-bump size and pitch
 - Wafer thickness, BEOL stack for 2.5D, RDL for 2.5D/3D, etc.
 - Standards: <http://wiki.sematech.org/3D-Standards>
- Enables economies of scale and faster adoption
 - EDA industry needs to be vocal

Die Stacking is an Enabler for System-Level Integration

- FPGAs have been gradually incorporating system-level functions
- Die stacking provides unique business opportunities
 - Moving up in value chain
 - Time-to-market and product differentiations
- EDA tools need to evolve to support higher-level system integration enabled by die-stacking

Thank You

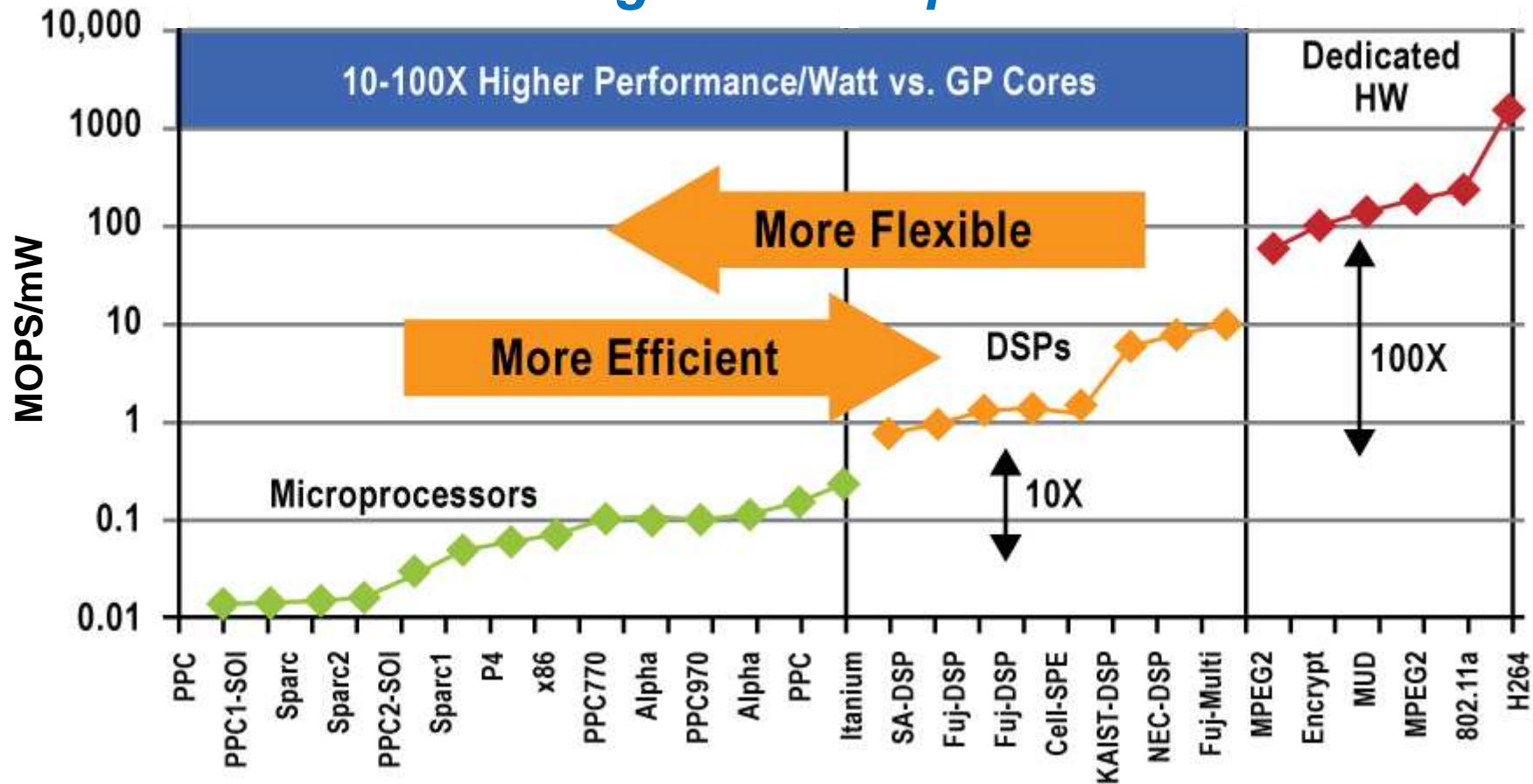
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The Dilemma: Flexibility vs. Efficiency

Reconfigurable Co-processors



Source: "High-performance Energy-Efficient Reconfigurable Accelerator Circuits for the Sub-45nm Era" July 2011 by Ram K. Krishnamurthy, Circuits Research Labs, Intel Corp.

Altera at a Glance



**Founded in Silicon Valley,
California in 1983**



**Industry's first reprogrammable
logic semiconductors**



\$1.95 billion in 2010 sales



2,600 employees



**Leading supplier of FPGAs,
ASICs and CPLDs**